Amendments to the Claims:

Claims 1- 6 (Canceled).

7. (Currently Amended) A method of forming a polymer optical waveguide pattern, comprising the steps of:

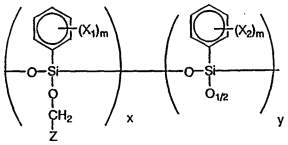
forming a core layer of a photosensitive composition ~~by a spin-coating method with~~ having a thickness of the core layer which ~~satisfies~~ achieves a single-mode ~~condition of a resulting~~ optical waveguide that comprises the core layer by a spin-coating method;

drying the photosensitive composition for optical waveguides;

irradiating said resultant photosensitive composition thin film for optical waveguides with light through a mask; and

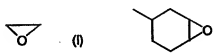
directly forming a core-ridge pattern by wet etching said photosensitive composition thin film;

wherein the photosensitive composition for optical waveguides comprises an organic oligomer and a polymerization initiator, said organic oligomer being a silicone oligomer represented by the following formula (2):



(2)

wherein X_1 and X_2 may be the same as or different from each other, and denote hydrogen, deuterium, halogen, an alkyl group or an alkoxy group; m is an integer from 1 to 5; x and y designate the proportion of respective units, and y is smaller than x and may be 0; and Z denotes an epoxy group shown in the following formula (I) or (II):



(I) (II).

Claims 8- 20 (Canceled).

21. (New) The method of forming a polymer optical waveguide pattern as claimed in Claim 7, wherein said thickness of the core layer is one in which birefringence after photocuring liquid oligomer in said photsenstive composition is less than 1×10^{-3}.